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## Robust Reduced Graphene-Oxide Paper Fabricated by Household Non-stick Frying pan: Large-area Freestanding Flexible Substrate for Supercapacitor†

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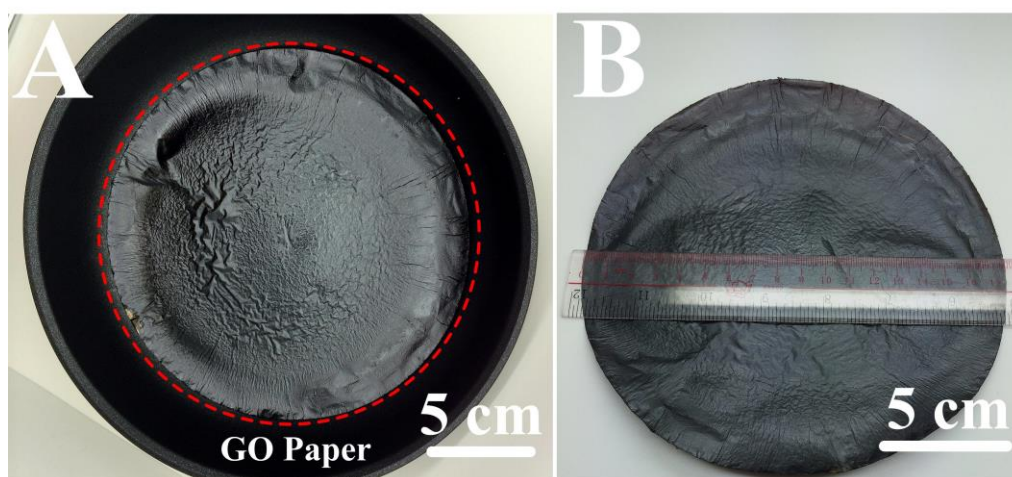


Fig. S1 Photographs of a round-shape GO paper up to 240 cm<sup>2</sup>: (A) in the non-stick frying pan and (B) peeling off from the pan.

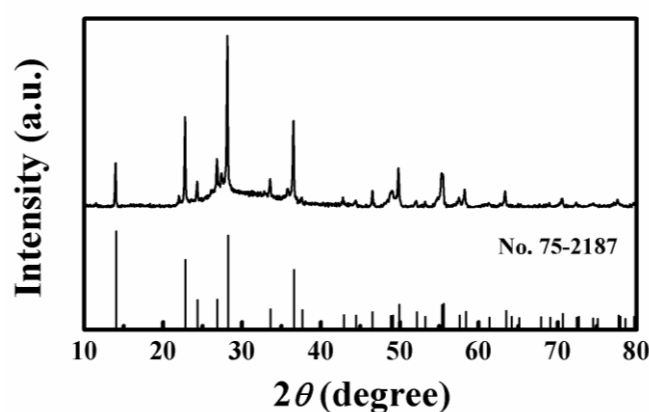


Fig. S2 XRD patterns of residual WO<sub>3</sub> particles.

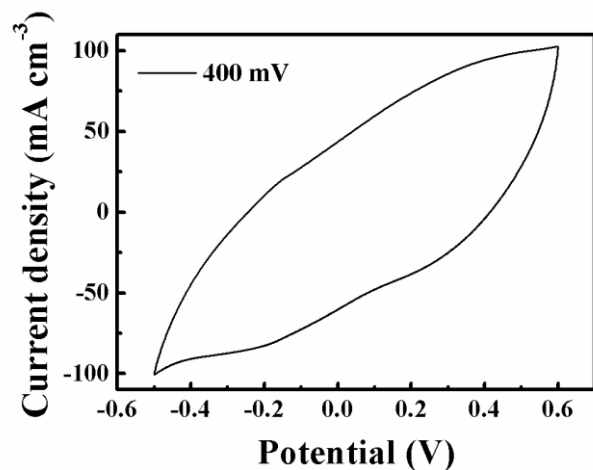


Fig. S3 Cyclic voltammogram (CV) of  $\text{WO}_3\text{-RGO/PPy-RGO}$  at a scan rate of  $400 \text{ mV s}^{-1}$ .

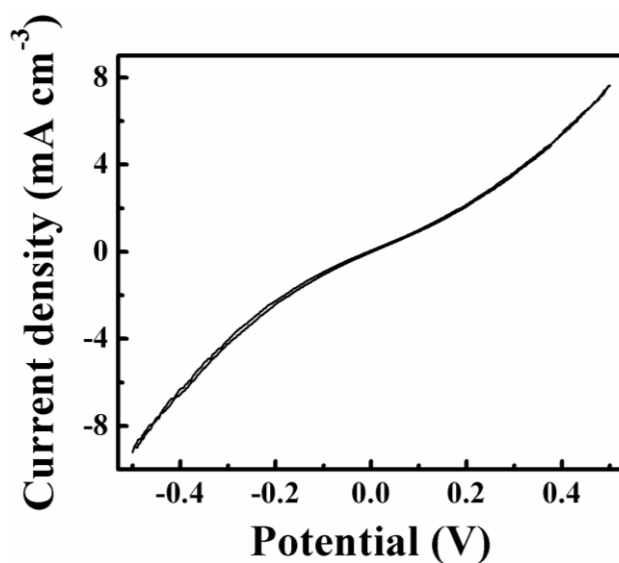


Fig. S4 CV of pure RGO symmetric supercapacitor at a scan rate of  $400 \text{ mV s}^{-1}$ , which exhibit a capacitance close to 0.

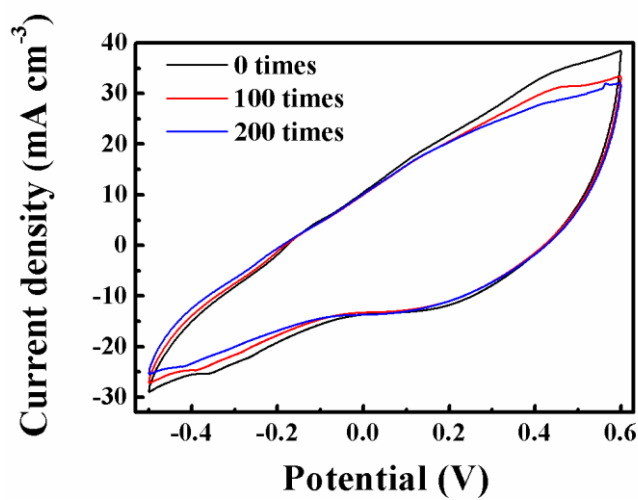


Fig. S5 CVs of  $\text{WO}_3\text{-RGO/PPy-RGO}$  at a scan rate of  $60 \text{ mV s}^{-1}$  with different bending times.